

The Impact of Electron-Phonon Coupling on the Figure of Merit of Ternary Monolayers

Nb₂SiTe₄ and Nb₂GeTe₄

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Table S1: The calculated relaxation times at room temperatures using deformation potential theory (DPT). The values of carrier mobilities and their effective masses are taken from the previous study.

Monolayer	carrier type	μ (cm ² /V.s)		m (m_e)		τ (10 ⁻¹³ s)	
		μ_{xx}	μ_{yy}	m_{xx}	m_{yy}	τ_{xx}	τ_{yy}
Nb ₂ SiTe ₄	hole	75.45	201	1.30	4.65	0.56	5.31
	electron	4570	4040	0.47	0.29	12.2	6.66
Nb ₂ GeTe ₄	hole	192	406	0.77	4.60	0.84	10.6
	electron	1910	2210	0.66	0.32	7.16	4.02

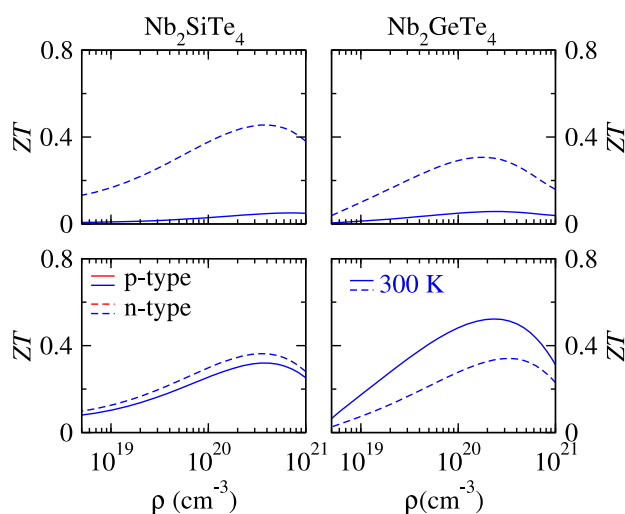


Fig. S1: The calculated figure of merit of Nb₂SiTe₄ and Nb₂GeTe₄ along x (1st row) and y (2nd row) direction. The values of τ are inserted as calculated with DPT.